

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)	ATTY. DOCKET NO. SEPP24.004AUS		APPLICATION NO. Unknown	
	APPLICANT To be provided			
	FILING DATE Herewith		GROUP Unknown	

FOREIGN PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
KMS	1	WO 02/27063 A2	04/04/02	PCT				

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)							
KMS	2	Shin et al., "Plasma-Enhanced Atomic Layer Deposition of SrTa ₂ O ₆ and SrBi ₂ Ta ₂ O ₉ Thin Films"; Atomic Layer Deposition (ALD 2002) Conference, Hanyang University, Seoul Korea, August 19-21, pp. 1-18 (2002)						
KMS	3	Williams et al. "Crystal Structure of Bi(OCMe ₂ CH ₂ OMe) ₃ and Its Use in the MOCVD of Bi ₂ O ₃ ***"; Chemical Vapor Deposition; pp. 205-206 (2001)						
KMS	4	Gordon et al. "Vapor Deposition of Metal Oxides and Silicates: Possible Gate Insulators for Future Microelectronics"; Chem. Mater.; Vol. 13; pp. 2463-2464 (2001)						
KMS	5	Ritala et al. Chapter 2, "Atomic Layer Deposition"; Handbook of Thin Film Materials; Vol. 1: Deposition and Processing of Thin Films; pp. 103-159 (2002)						

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EXAMINER	/Kelly Stouffer/	DATE CONSIDERED	07/27/2006
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